

**PATENT** 

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re th	ne application of	)	
Julia S. SVIRCHEVSKI et al.		)	Group Art Unit: 1765
Application No. 09/336,401		)	Examiner: L. Umez-Eronini
Filed:	June 18, 1999 (CPA filed 11/27/2001)	)	Attorney Docket No. LAM1P109
For:	POST-PLASMA PROCESSING WAFER CLEANING METHOD AND SYSTEM	) ) )	Date: May 20, 2002

**CERTIFICATE OF MAILING** 

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, DC 20231 on May 20, 2002.

Commissioner for Patents Washington, D.C. 20231

Dear Sir:

To Tallo Applicants submit this paper in response to the Office Action dated December 19, 2001. A response to this Office Action was due on March 19, 2002. Accordingly, Applicants are concurrently submitting a request for a two-month extension of the period for response. Please amend this application as follows:

## IN THE CLAIMS:

Please amend claim 6 as indicated below. Attached hereto as a separate page is a "marked-up" version of claim 6 that show the changes made to this claim. For the Examiner's convenience, all pending claims are reproduced below, with the claim that has been amended herein being indicated as such.

06/10/2002 ADSMAN1 00000014 09336401

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